

**CLAIM AMENDMENTS:**

Claims 1-3 (canceled).

Claim 4 (previously presented): A photoresist applying device, comprising:  
an air-bubble collecting part provided on a photoresist flow passage at a predetermined part of a nozzle pipe directly connected to a nozzle tip;  
wherein the nozzle pipe is in such a shape as continuing in a rise part, a horizontal part and a fall part; and  
wherein a curved part is made at between the rise part and the fall part, the curved part having a top dead center serving as the air-bubble collecting part.

Claims 5 and 6 (canceled).

Claim 7 (original): A photoresist applying device according to claim 4, wherein graduations are provided on a pipe outer wall close to the top dead center.

Claim 8 (original): A photoresist applying device according to claim 7, wherein a staying amount of air bubble requiring air-bubble removal is previously defined and a size of air bubble is measured by the graduations as required.

Claim 9 (original): A photoresist applying device according to claim 4, wherein the curved part of the nozzle pipe is fixed and supported by a jig.

Claim 10 (currently amended): A photoresist applying device, comprising:  
a nozzle pipe having a first end and a second end, through which photoresist flows in a direction from the first end to the second end; and  
a nozzle tip connected to the second end of said nozzle pipe, and through which the photoresist is discharged after flowing through said nozzle pipe;  
wherein said nozzle pipe has an air-bubble collecting part disposed between the first end and the second end, and through which the photoresist flows prior to being discharged through said nozzle tip.

Claim 11 (previously presented): A photoresist applying device according to claim 10, wherein the nozzle pipe has a rise part, a horizontal part, a fall part and a curved part disposed between the rise part and the fall part, the curved part having a top dead center serving as the air-bubble collecting part.

Claim 12 (currently amended): A photoresist applying device according to claim 10, further comprising a valve connected to the first end of said nozzle pipe, and a supply pipe connected to the valve, the photoresist flowing from the supply pipe, through the valve, through the nozzle pipe and through the nozzle tip, respectively.

Claim 13 (previously presented): A photoresist applying device according to claim 12, wherein the valve is a suck-back valve.